

ABSTRACT OF THE DISCLOSURE

A laser CVD device capable of tightening adhesion of a film formed by laser CVD to a film formation face of a substrate and preventing cracks from occurring in the film itself is to be provided. The device comprises a plasma pretreating unit for turning
5 pretreating gas into a plasma state by arc discharge and for supplying the plasma state gas to the film formation face; and a film forming unit having means for sealing film forming gas while being isolated from an external atmosphere, means for radiating a laser beam to the film forming gas, wherein the film is formed over the film formation face of the substrate.